

ABSTRACT

6/27/03
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A manufacturing method for exposure apparatuses is provided in which a reticle R1 held on a reticle stage system (RST) is illuminated by exposure light from an exposure light source (16) via the illumination systems (IL1) and (IL2). In a first manufacturing line, a main body module composed of a frame caster (2), a main body support section (3), and a main body column (5) is assembled, and an illumination system and the projection optical system PL are mounted on this main body module. Then a stage module, which is assembled and adjusted using another main body module in a second manufacturing line, is mounted on the main body module of the first manufacturing line. Therefore exposure apparatuses can be efficiently manufactured without using dedicated large scale adjustment jigs.

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